

ABSTRACT

POLISHING PAD AND METHOD FOR PRODUCING SAME

An object of the present invention is to provide a
5 polishing pad capable of maintaining a high level of dimensional
stability upon moisture absorption or water absorption though
it has high water absorption property and which hardly causes
scratches on the surface to be polished of an object to be
polished, and a method for producing the same. A polishing pad
10 having a polishing layer comprising a polyurethane foam having
fine cells, wherein the polyurethane foam includes a reaction
cured body of a polyurethane raw material composition
containing (1) an isocyanate-terminated prepolymer (A)
obtained by reacting a prepolymer raw material composition (A')
15 containing an isocyanate monomer, a high molecular weight
polyol (a) and a low molecular weight polyol, (2) an
isocyanate-terminated prepolymer (B) obtained by reacting a
prepolymer raw material composition (B') containing a
polymerized diisocyanate and a high molecular weight polyol (b),
20 and (3) a chain extender; and the polymerized diisocyanate
contains pentamers or higher oligomers in an amount of 40% by
weight or less.